

Fig. 4-5 SEM micrographs of CW laser crystallized poly-silicon films after Secco etching for 60sec treatment. The applied laser power is 1W. The scan speed is constant for 2.5cm/sec, pre treatment clean with HF+O3 condition

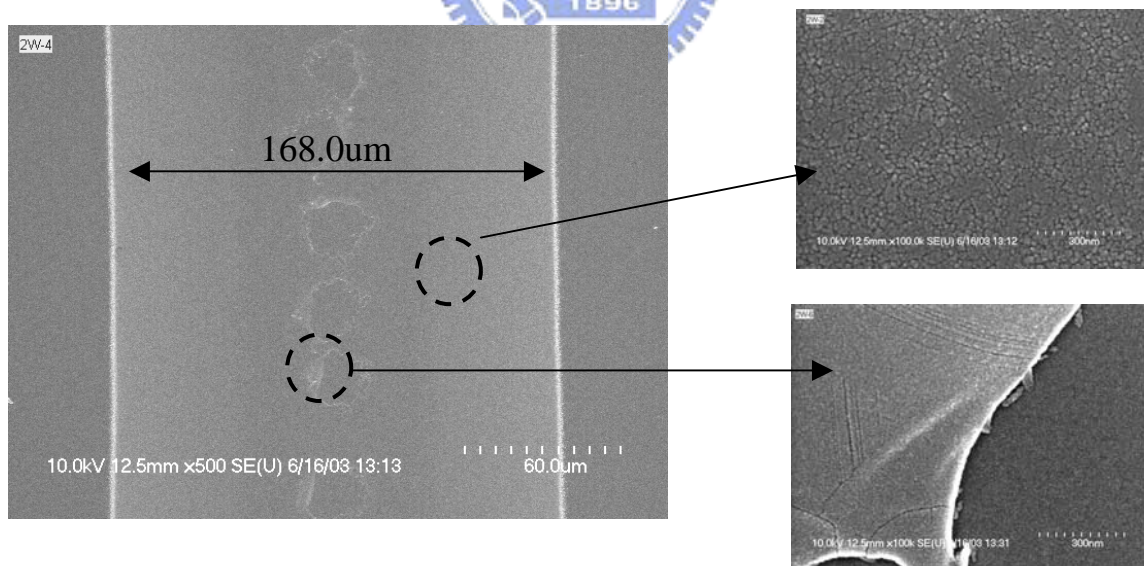


Fig. 4-6 SEM micrographs of CW laser crystallized poly-silicon films after Secco etching for 60sec treatment. The applied laser power is 2W. The scan speed is constant with 2.5cm/sec, pre treatment clean with HF+O3 condition

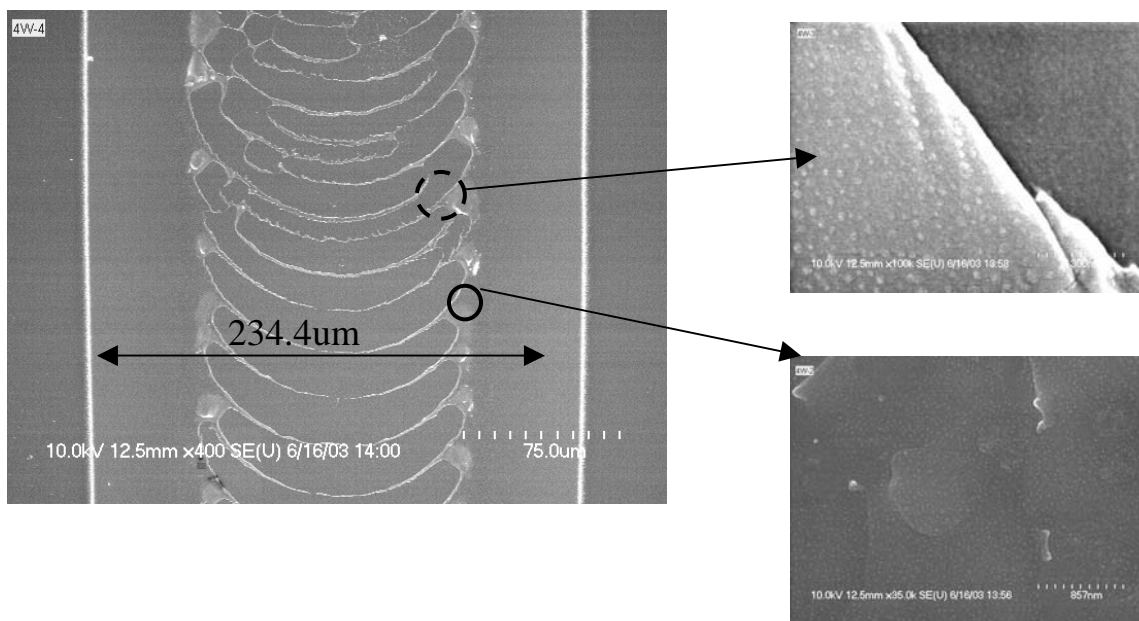


Fig. 4-7 SEM micrographs of CW laser crystallized poly-silicon films after Secco etching for 60sec treatment. The applied laser power is 4W. The scan speed is constant with 2.5cm/sec, pre treatment clean with HF+O3 condition

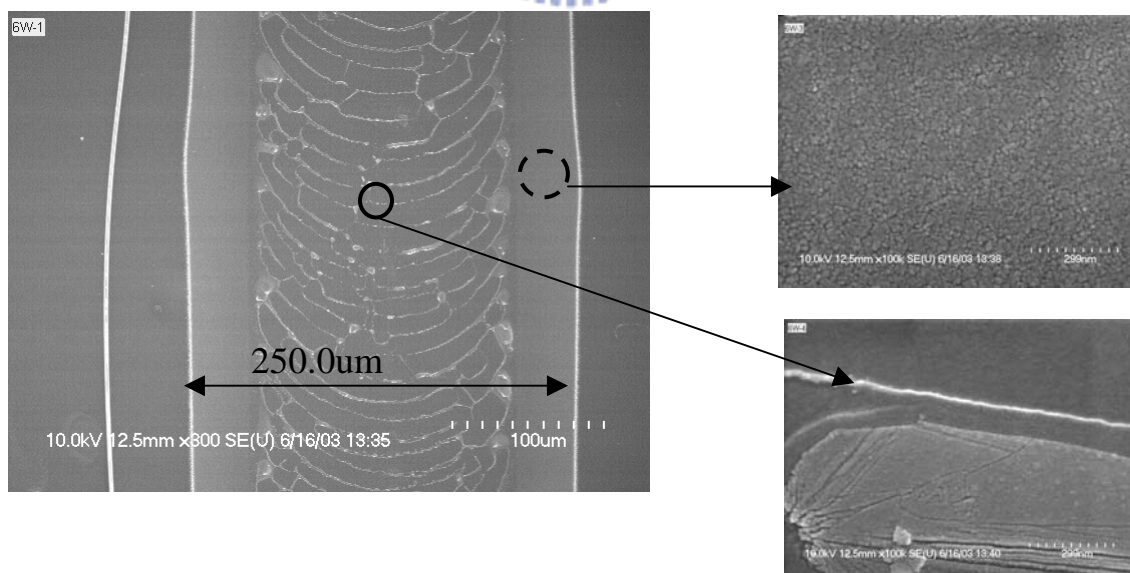
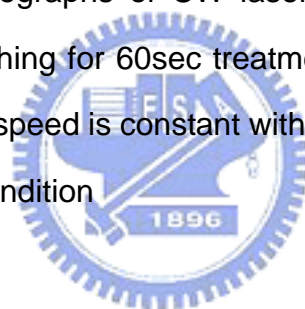


Fig. 4-8 SEM micrographs of CW laser crystallized poly-silicon films after Secco etching for 60sec treatment. The applied laser power is 6W. The scan speed is constant for 2.5cm/sec, pre treatment clean with

HF+O3 condition

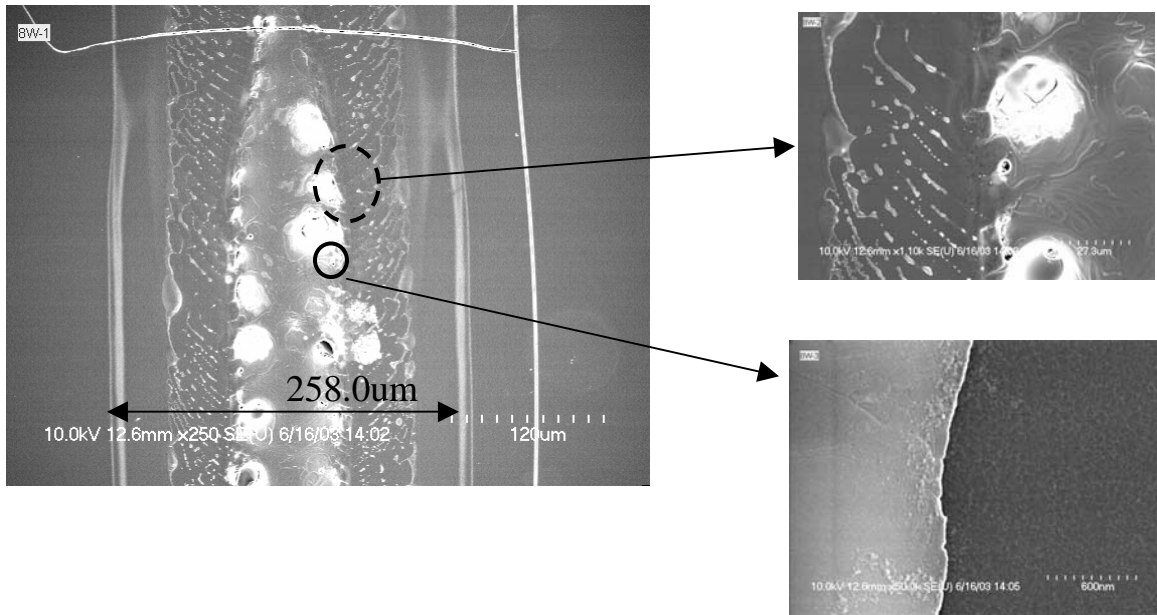


Fig. 4-9

SEM micrographs of CW laser crystallized poly-silicon films after Secco etching for 60sec treatment. The applied laser power is 8W. The scan speed is constant for 2.5cm/sec, pre treatment clean with HF+O3 condition

